## Homework #7 - EE 482 due Monday 2/28/11

- 1. An MOS capacitor is made on n-type silicon with an oxide thickness of 10nm, a positive interface charge of  $Q'_{ss}/q = 5 \times 10^{10} \,\mathrm{cm}^{-2}$  and a uniform positive oxide charge density of  $\rho_{ox}/q = 2 \times 10^{16} \,\mathrm{cm}^{-3}$  throughout the oxide. The substrate is doped with  $N_d = 10^{17} \,\mathrm{cm}^{-3}$  and the gate is polysilicon doped with boron just to the edge of degeneracy  $(p^+ \text{ poly}, E_f = E_v)$ .
  - (a) Calculate the flat-band voltage  $V_{FB}$  and the threshold voltage  $V_T$ .
  - (b) Sketch the charge density, electric field and energy-band diagram at flat-band and at the edge of strong inversion.
  - (c) Sketch the high and low frequency capacitance as function of  $V_{gb}$ .  $C'_{min}$ ,  $C'_{acc}$  and  $C'_{inv}$  should calculated and indicated on the sketch.
- 2. Consider a gated MOS capacitor with a *p*-type silicon substrate doped with  $10^{18}$  cm<sup>-3</sup>, a heavily-doped *n*-type channel contact, a 2 nm thick gate oxide, and an arsenic-doped gate with  $E_f = E_c$ .
  - (a) Calculate and plot the depletion charge and inversion charge as function of voltage dropped across the semiconductor for  $V_{CB} = 0$  and  $V_{CB} = 1V$ .
  - (b) Under the same conditions as in (a), calculate and plot the voltage dropped across the oxide and the associated gate to channel voltage  $(V_{GC})$ . Don't forget to account for work function difference.
  - (c) Calculate the threshold voltage (value of  $V_{GC}$  for which *n* at surface equals *p* in bulk) for each case. Comment on how the inversion charge varies with  $V_{GC}$  above threshold based on (a) and (b). For  $V_{CB} = 1V$ , sketch the band diagram from gate to substrate in inversion.
- 3. An *n*-channel silicon MOS transistor with a polysilicon gate doped to the edge of degeneracy with phosphorus  $(E_f = E_c)$  has doping of  $N_a = 10^{18} \text{cm}^{-3}$  in the substrate,  $x_{ox} = 4 \text{ nm}$  and  $W = 2L = 1.0 \mu \text{m}$ . Assume oxide charges can be ignored.
  - (a) Find the threshold voltage with  $V_{SB} = 0$ .
  - (b) Calculate  $\delta$ , the correction term for change in depletion charge as  $V_{CB}$  increases, in the improved square-law drain current equation:

$$I_D = \frac{W}{L} \mu'_n C'_{ox} \left[ (V_{GS} - V_T) V_{DS} - \frac{(1+\delta)V_{DS}^2}{2} \right]$$

An appropriate value is  $\delta = (1/C_{ox})(dQ_d^{max}/V_{CB}) = C_s^{depl}/C_{ox}$  determined near threshold with  $V_{CB} = 0$ .

- (c) Plot  $I_{DS}$  versus  $V_{DS}$  for  $V_{GS} = 3V$  and  $V_{SB} = 0$  using the three linear-region drain current equations  $(\delta = 0, \delta \text{ as above, and Eq. (9) in notes})$ . Include  $V_{DS}$  values at least up to saturation.
- (d) Using the linearized equation and  $\delta$  as calculated, determine the operating regime and drain current under the following conditions. In each case, sketch the band diagram at the drain end of the channel.
  - i.  $V_S = 0, V_B = 0V, V_G = 3V, V_D = 1V.$
  - ii.  $V_S = 0, V_B = 0V, V_G = 3V, V_D = 3V.$
  - iii.  $V_S = 0, V_B = 0V, V_G = 0V, V_D = 3V.$